

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S129	26	(kirimura near2 hiroya or kiyoshi near2 ogata).in. and laser near10 crystal\$7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:16
L2	17	1 and "without"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:16
L1	26	(kirimura near2 hiroya or kiyoshi near2 ogata).in. and laser near10 crystal\$7	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:16
L5	2	1 and "without" near4 dehydrogenation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:18
L3	2	1 and "without" near4 hydrogen	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:18
L7	472	laser near10 crystal\$6 and ion near5 beam near10 deposit\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:20
L6	1593	laser near10 crystal\$6 and ion near10 deposit\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:20
L4	41280	laser near10 crystal\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:20
S15	83	laser same anneal\$3 same (silicon or si) and "117"/\$4.ccls. and (CVD or chemical adj vapor adj deposition) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:21

## EAST Search History

L9	24	laser near10 crystal\$6 and ion near5 beam near10 deposit\$5 near10 (si or silicon) and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:21
L8	191	laser near10 crystal\$6 and ion near5 beam near10 deposit\$5 and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:21
L10	127	laser same anneal\$3 same (silicon or si) and "117"/\$4.ccls. and (CVD or chemical adj vapor adj deposition) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:33
S61	165	without near4 hydrogen near15 (si or silicon) near2 (layer film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:34
S17	78	laser same anneal\$3 same (silicon or si) and "117"/\$4.ccls. and (CVD or chemical adj vapor adj deposition) same plasma same (si or silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:34
L12	200	without near4 hydrogen near15 (si or silicon) near2 (layer film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:34
L11	120	laser same anneal\$3 same (silicon or si) and "117"/\$4.ccls. and (CVD or chemical adj vapor adj deposition) same plasma same (si or silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/02 19:34